SEP 20 2006

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant:

Weis, et al.

Docket No.:

02P15178US/INTECH 3.0-079

Serial No.:

10/774,827

Art Unit:

2822

Filed:

February 9, 2004

Examiner:

Trinh, Michael Manh

For:

Line Mask Defined Active Areas for 8F2 DRAM Cells with Folded Bit Lines

and Deep Trench Patterns

Mail Stop Amendment Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

AMENDMENT ACCOMPANYING RCE

Dear Sir:

The following amendments and remarks are presented in response to the Examiner's Office Action mailed June 14, 2006. Please amend the above-referenced application as follows.